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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Cheng-Ku CHEN, et al.

Serial No.: 10/798,178

Filed: March 11, 2004

For: METHOD OF FORMING
POLYSILICON GATE STRUCTURES
WITH SPECIFIC EDGE PROFILES FOR
OPTIMIZATION OF LDD OFFSET
SPACING

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Confirmation No. 5314

Group Art Unit: 2812

Examiner: Cheung Lee

Commissioner for Patents
Mail Stop Amendment
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

In response to the Office Action dated October 18, 2005, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 10 of this paper.